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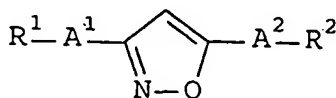
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(TTT)

(57) Abstract: The present invention relates to a process for preparing a pharmaceutical starting compound compound by hydrolyzing a compound of the general formula (II): Wherein R<sup>1</sup> is protected carboxy, R<sup>2</sup> is lower alkoxy or higher alkoxy, A<sup>1</sup> is an aromatic bivalent group, heterocyclic bivalent group or cyclo (lower) alkane bivalent group, and A<sup>2</sup> is an aromatic bivalent group, heterocyclic bivalent group or cyclo (lower) alkane bivalent group, with aqueous potassium hydroxide and by treating with hydrochloric acid.